

Interference Search Notes

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	51	((damascene or dual-damascene or intermetal near dielectric or inter-metal near dielectric) and (c-oxide c-sio or (carbon) near2 (doped or doping) near2 (oxide or silicon adj oxide or silicon adj dioxide or sio) or carbon-oxide or "c:sio")).clm.	US-PGPUB	OR	ON	2006/01/27 17:07
L2	0	((damascene or dual-damascene or intermetal near dielectric or inter-metal near dielectric) and (partial or partially) near (organic or inorganic)).clm.	US-PGPUB	OR	ON	2006/01/27 17:08
L3	6	((damascene or dual-damascene or intermetal near dielectric or inter-metal near dielectric) and (hybrid near2 organic near2 inorganic)).clm.	US-PGPUB	OR	ON	2006/01/27 17:09
L4	21	((damascene or dual-damascene or intermetal near dielectric or inter-metal near dielectric) and (copper or cu) and barrier and (sio or silicon adj oxide or silicon adj dioxide or inorganic) and (carbon or c! or organic) near2 (doped or containing) near2 (oxide or sio or inorganic)).clm.	US-PGPUB	OR	ON	2006/01/27 17:12
L5	123	((damascene or dual-damascene or intermetal near dielectric or inter-metal near dielectric) and (trench or line) adj (first or before or prior)).clm.	US-PGPUB	OR	ON	2006/01/27 17:12
L6	33	((damascene or dual-damascene or intermetal near dielectric or inter-metal near dielectric) and (trench or line) adj (first or before or prior) near5 (via or hole or contact)).clm.	US-PGPUB	OR	ON	2006/01/27 17:12

EAST - text search notes

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	35	"5821168".pn. "5960320".pn. "5904565".pn. "5705430".pn. "5969422".pn. "5635423".pn. "6207577".pn. "6255735".pn. "6277733".pn. "677574".pn. "6410394".pn. "6054379".pn. "6211063".pn. "5989623".pn. "6043167".pn. "6197696".pn. "6110648".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/27 14:23
L2	2907	damascene and (trench) near3 (first or prior or earlier or before)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/27 13:18
L4	192	damascene and trench-first	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/27 13:34
L5	1209	(damascene or dual-damascene) and (trench-first or trench adj first or (trench or line) near3 (etch or etching or etched) near3 (prior or before or earlier or preceding or after or later) near3 (via or hole) near2 (etch or etching or etched))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/27 13:36
L7	1094	(damascene or dual-damascene) and (trench-first or trench adj first or (via or hole) near2 (etch or etched or etching) near4 (within or inside or bottom) near4 (trench))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/27 13:38
L8	645	(damascene or dual-damascene) and (trench-first or trench adj first or (via or hole) near2 (etch or etched or etching) near4 (within or inside or bottom) near4 (trench)) and (sic or si-c or c-oxide or carbon near oxide or organosilicate or organic or sioc or sico or sicoh or sioch)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/27 13:39
L9	42	("20010046567" "20030017642" "20030024902" "4808259" "4900591" "5204141" "5262279" "5302236" "5356515" "5360646" "5389581" "5486493" "5488015" "5492736" "5559055" "5591677" "5593741" "5660738" "5679608" "5700720" "5789319" "5807785" "5834847" "5908672" "5968324" "6035803" "6054206" "6077764" "6083852" "6124641" "6127262" "6140226" "6147009" "6156149" "6159871" "6169021" "6211092" "6287990" "6451683" "6509258" "6514667" "6573572").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2006/01/27 13:49
L10	2	("5604156" "5882996").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2006/01/27 13:57
L11	2	"6340435".pn. "6054379".pn.	US-PGPUB; USPAT; USOCR	OR	ON	2006/01/27 13:57
L12	25	("4900591" "5204141" "5262279" "5302236" "5356515" "5360646" "5486493" "5488015" "5492736" "5559055" "5591677" "5593741" "5660738" "5679608" "5700720" "5789319" "5807785" "5843847" "6054206" "6124641" "6140226" "6147009" "6159871" "6169021" "6287990").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2006/01/27 13:59
L13	416	(damascene or dual-damascene or (inter-metal or intermetal) near2 (dielectric or wiring)) same (carbon near oxide or c-oxide or organosilicate or sicoh or sioch or sico or sioc or si near c near o near h)	US-PGPUB; USPAT; USOCR	OR	ON	2006/01/27 14:01
L14	178	(damascene or dual-damascene or (inter-metal or intermetal) near2 (dielectric or wiring)) same (carbon near oxide or c-oxide or organosilicate or sicoh or sioch or sico or sioc or si near c near o near h) and (sio or silicon near oxide or silicon near dioxide or sin or silicon near nitride or sion or oxynitride) near5 (barrier or etch near stop or etching near stop or via or contact or hole)	US-PGPUB; USPAT; USOCR	OR	ON	2006/01/27 14:38

L15	6	("5635423" "5705430" "5821168" "5904565" "5960320" "5969422").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2006/01/27 14:12
L16	2632	438/622.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/27 14:40
L18	43	438/622.ccls. and (trench or line) near3 (first or prior or earlier or before) near3 (etch or etched or etching) near3 (via or hole or contact)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/27 14:40
L19	66	438/622.ccls. and (c-oxide c-sio or (carbon) near2 (doped or doping) near2 (oxide or silicon adj oxide or silicon adj dioxide or sio) or carbon-oxide or "c:sio")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/27 14:50
L20	253	(damascene or dual-damascene or (inter-metal or intermetal) near2 (dielectric or wiring)) same (c-oxide c-sio or (carbon) near2 (doped or doping) near2 (oxide or silicon adj oxide or silicon adj dioxide or sio) or carbon-oxide or "c:sio")	US-PGPUB; USPAT; USOCR	OR	ON	2006/01/27 14:40
L21	753	438/623.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/27 14:54
L22	8	438/623.ccls. and (trench or line) near3 (first or prior or earlier or before) near3 (etch or etched or etching) near3 (via or hole or contact)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/27 14:54
L23	44	438/623.ccls. and (c-oxide c-sio or (carbon) near2 (doped or doping) near2 (oxide or silicon adj oxide or silicon adj dioxide or sio) or carbon-oxide or "c:sio")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/27 14:57
L24	3020	438/624.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/27 14:54
L25	35	438/624.ccls. and (trench or line) near3 (first or prior or earlier or before) near3 (etch or etched or etching) near3 (via or hole or contact)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/27 15:04
L26	57	438/624.ccls. and (c-oxide c-sio or (carbon) near2 (doped or doping) near2 (oxide or silicon adj oxide or silicon adj dioxide or sio) or carbon-oxide or "c:sio")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/27 15:08
L27	950	438/627.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/27 15:12
L28	11	438/627.ccls. and (trench or line) near3 (first or prior or earlier or before) near3 (etch or etched or etching) near3 (via or hole or contact)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/27 15:12

L29	44	438/627.ccls. and (c-oxide c-sio or (carbon) near2 (doped or doping) near2 (oxide or silicon adj oxide or silicon adj dioxide or sio) or carbon-oxide or "c:sio")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/27 15:23
L30	2497	438/637.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/27 15:37
L31	70	438/637.ccls. and (trench or line) near3 (first or prior or earlier or before) near3 (etch or etched or etching) near3 (via or hole or contact)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/27 15:37
L32	101	438/637.ccls. and (c-oxide c-sio or (carbon) near2 (doped or doping) near2 (oxide or silicon adj oxide or silicon adj dioxide or sio) or carbon-oxide or "c:sio")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/27 15:43
L33	902	438/638.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/27 15:37
L34	59	438/638.ccls. and (trench or line) near3 (first or prior or earlier or before) near3 (etch or etched or etching) near3 (via or hole or contact)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/27 15:38
L35	67	438/638.ccls. and (c-oxide c-sio or (carbon) near2 (doped or doping) near2 (oxide or silicon adj oxide or silicon adj dioxide or sio) or carbon-oxide or "c:sio")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/27 15:44